Significance of STEM-EDXS Analysis in the Characterization of Rechargeable Battery Components

Guest speaker: Michael Malaki

Significance of STEM-EDXS Analysis in the Characterization of Rechargeable Battery Components

Dr. Igor Németh
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Bruker Nano Analytics

Michael Malaki
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Materials Sciences Center
Faculty of physics
Phillips University Marburg

Outline

- EDS instrumentation for battery research

  Igor Németh
  Bruker Nano Analytics

- Significance of STEM-EDXS Analysis in the Characterization of Rechargeable Battery Components

  Michael Malaki
  Phillips University Marburg

- Comparison of STEM-EDS and SEM-EDS

  Igor Németh
  Bruker Nano Analytics

Bruker Nano GmbH,
EDS instrumentation for battery research

Dr. Igor Németh

Requirements, tools and methods of EDS analysis for battery research

- High solid angle X-ray collection in SEM and in STEM
  -> sufficient data quantity for thin FIB lamellae samples
- Hypermap: measure data and process later
  -> element distribution maps, line profiles
- Deconvolution:
  -> Real distribution maps (also for overlapping peaks)
  -> Quantification of spectra and maps
- In situ measurements: EDS at elevated temperatures

Geometric constraints in SEM and STEM:
Solid and take-off angle are important to consider!

Tools of EDS analysis: Hypermap

BSE Al Mg S

50 µm

channel

Save data as **Hypermap** and **process later**:

Extract spectra:

-> prove presence/absence of elements

-> Calculate quantitative concentration values

Extract line profiles:

-> Quantitative line profiles

Quantitative element distribution maps

Tools of EDS analysis: Deconvolution

1. Background fitting

cps/eV

Energy [keV]

Tools of EDS analysis: Deconvolution

cps/eV

Energy [keV]

C O Ni Ga Al W Co Cu W Ti Mn Mg S Ti Mn Co Ni Cu W Ga

1. Background fitting
2. Background subtraction

Tools of EDS analysis: Deconvolution

cps/eV

Energy [keV]

1. Background fitting
2. Background subtraction
3. Deconvolution:
   assign counts to elements

Tools of EDS analysis: Deconvolution

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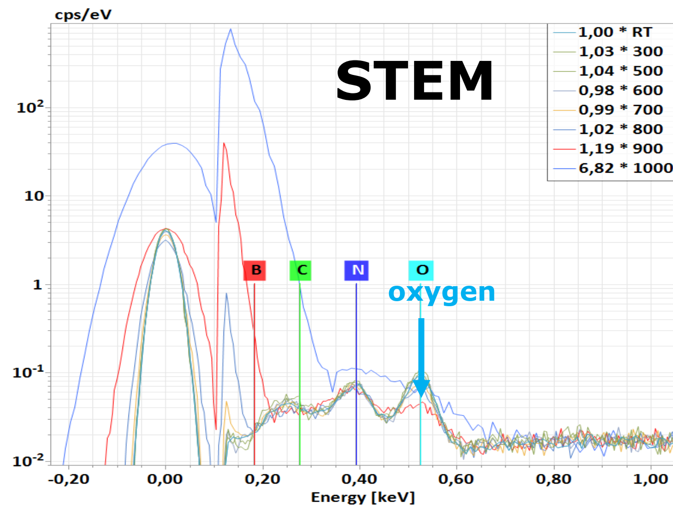
Tools of EDS analysis: Deconvolution

cps/eV

Energy [keV]

1. Background fitting
2. Background subtraction
3. Deconvolution:
   assign counts to elements
4. Net counts:
   -> quantification OR
   -> element distribution maps

EDS in situ / at elevated temperatures



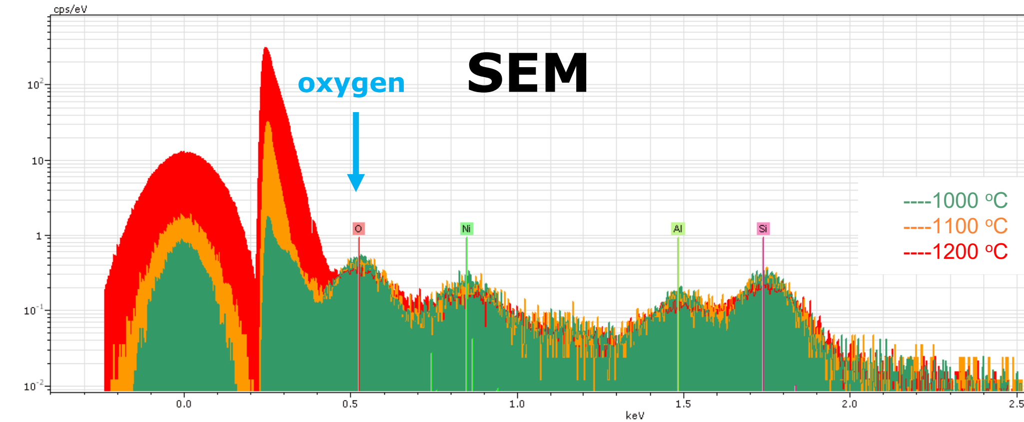
TEM: 11mm sample – detector distance

Challenges:

Thermal radiation -> noise -> high background below 2keV: detection of light elements affected

This effect depends on:

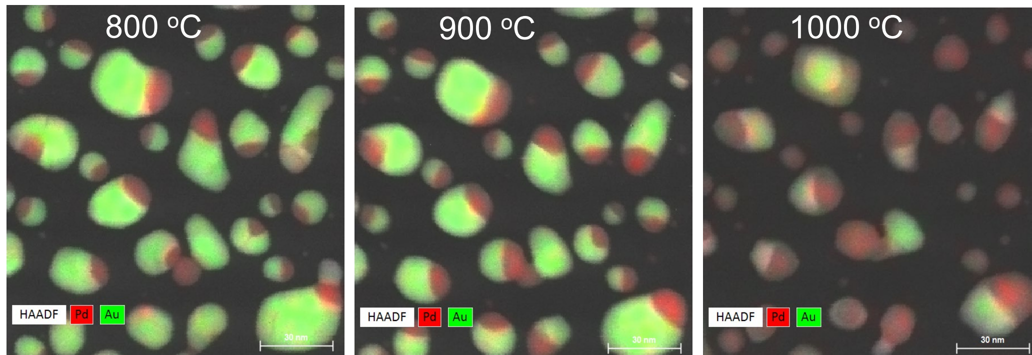
- sample-detector distance
- detector window material



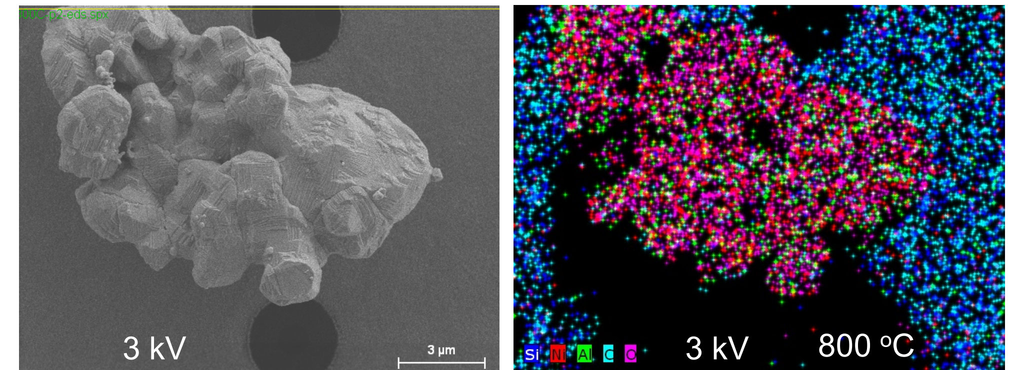
SEM: 25mm sample – detector distance

Possibilities:

- Spectra: monitoring of element lines
- Mapping: Phase changes, segregations



J. T. van Omme et al., Ultramicroscopy 192 (2018) 14–20



Jane Y. Howe (ORNL), Christianne Beekman (Florida St. Uni)

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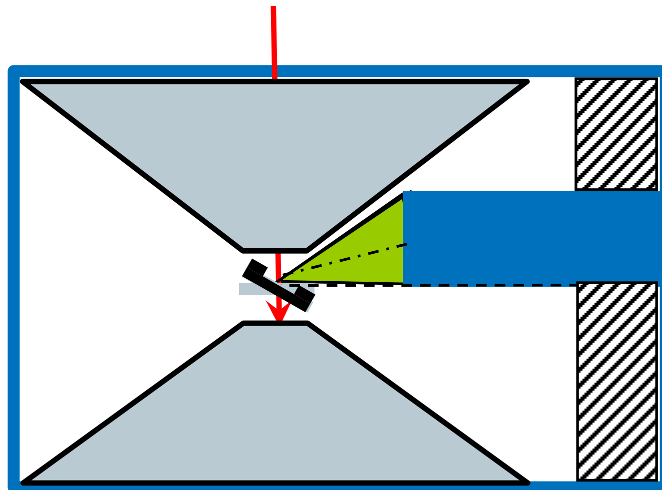
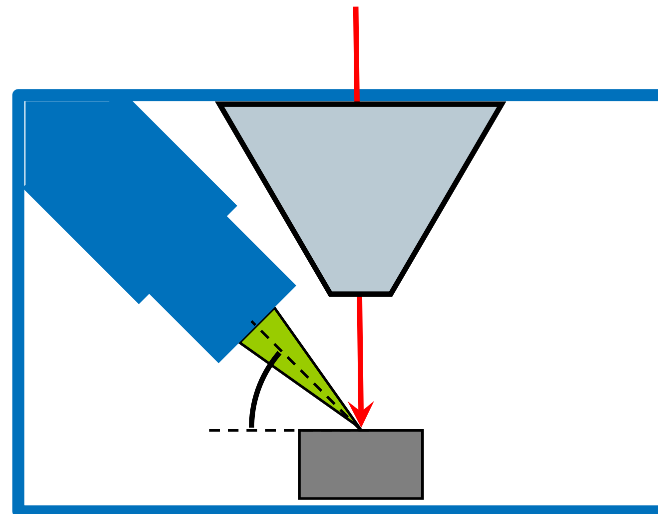
Comparison of the same sample STEM - SEM

STEM 200kV
60 mm² EDS detector



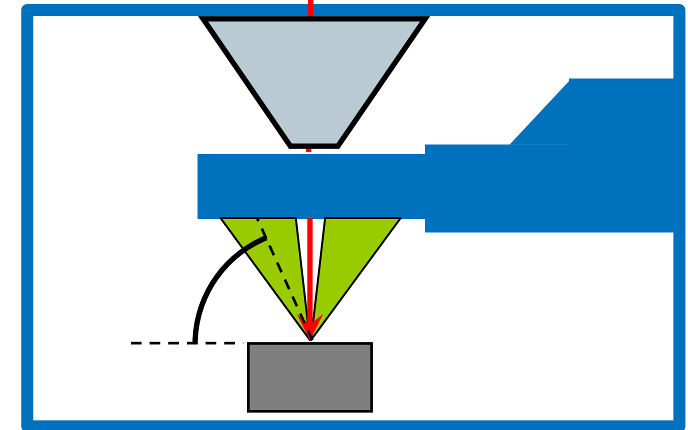
take off angle=22°
solid angle~0.26sr
beam current~0.05 nA

SEM 20kV
60 mm² EDS detector
@WD= 8mm



take off angle=35°
solid angle=0.043 sr
beam current~ 2nA

SEM 20kV
60 mm² 4x15mm²
FlatQUAD detector
@WD=16mm



take off angle=60-70°
solid angle= 0.7-1 sr
beam current~ 2nA

x7 more X-ray signal

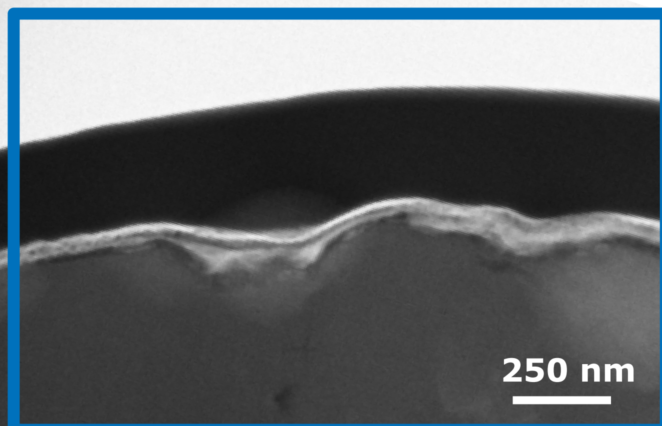
x15-20 more X-ray signal

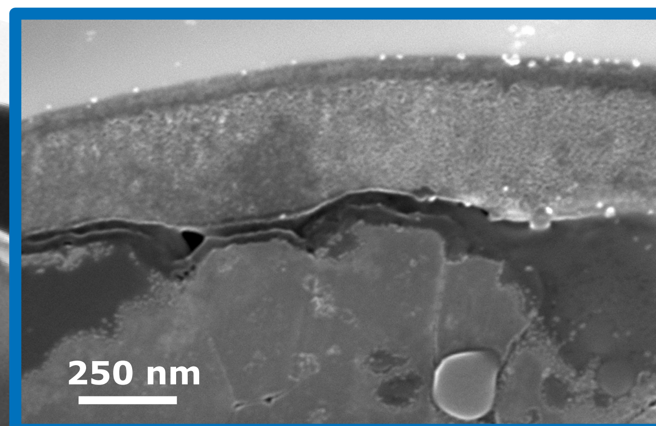
Comparison of the same sample STEM - SEM

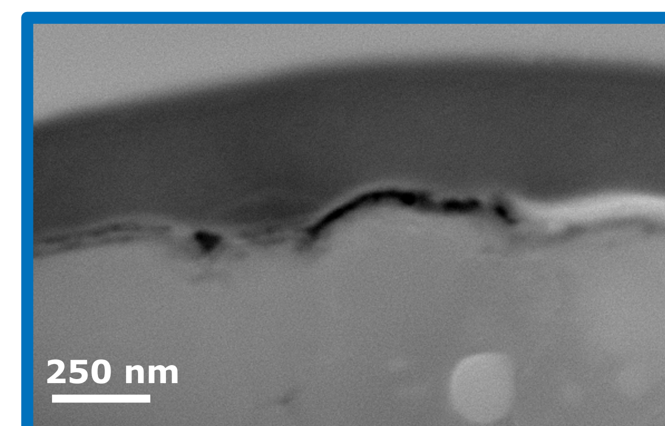
STEM 200kV
HAADF image

SEM 20kV
In-lens image
WD=8mm

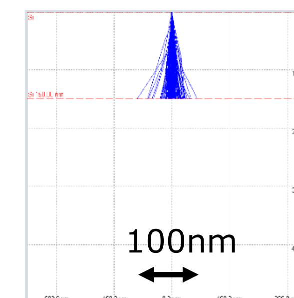
SEM 20kV
SE image with
inserted FlatQUAD
WD=16mm







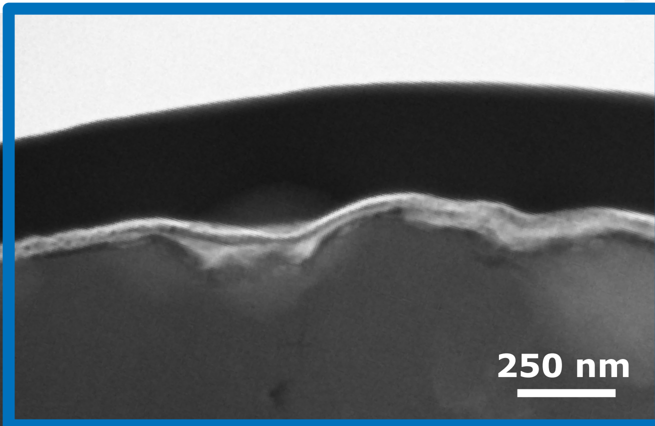
Images taken under measurement conditions optimized for EDS analysis
Image quality does not affect EDS resolution on this scale!



Sample and data courtesy: Michael Malaki, Shamail Ahmed, Materials Sciences Center, Philipps University Marburg

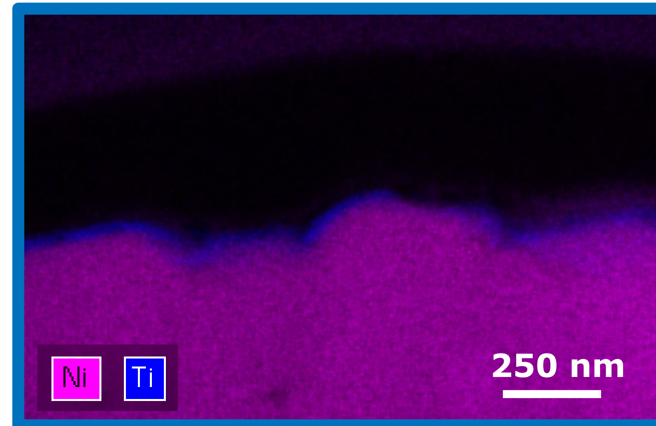
Comparison of the same sample STEM - SEM

STEM 200kV
60 mm² EDS detector



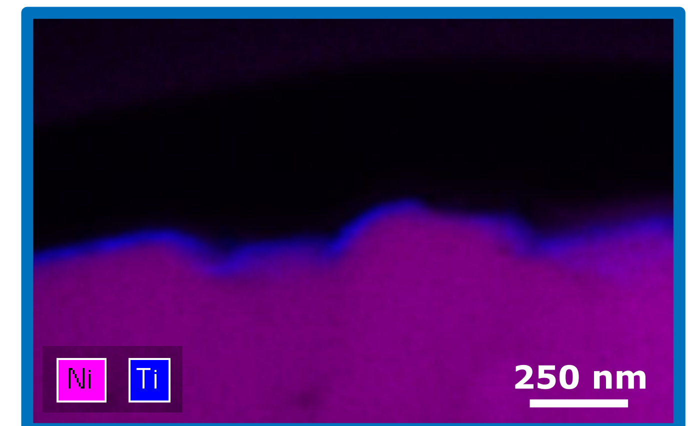
Total measurement time= 8 mins
Beam current= 0.2 nA
Input count rate ~ 1 kcps

SEM 20kV
60 mm² EDS detector



Total measurement time= 34 mins
Beam current=2 nA
Input count rate ~ 30 kcps

SEM 20kV
FlatQuad detector

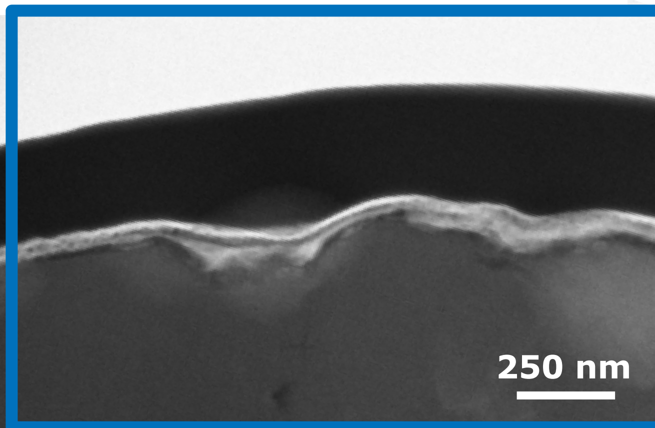


Total measurement time= 34 mins
Beam current= 2 nA
Input count rate ~ 460 kcps

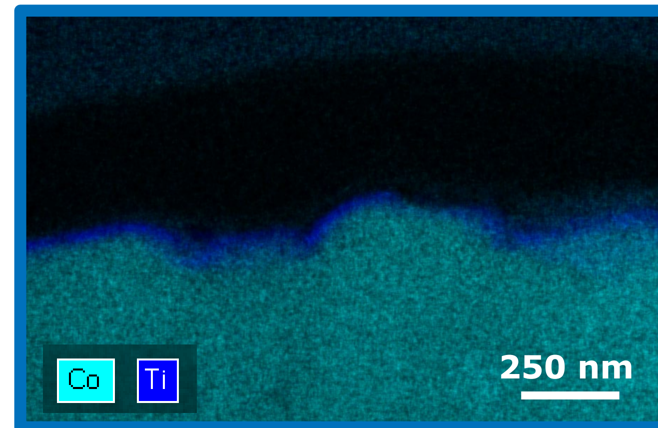
Sample and data courtesy: Michael Malaki, Shamail Ahmed, Materials Sciences Center, Philipps University Marburg

Comparison of the same sample STEM - SEM

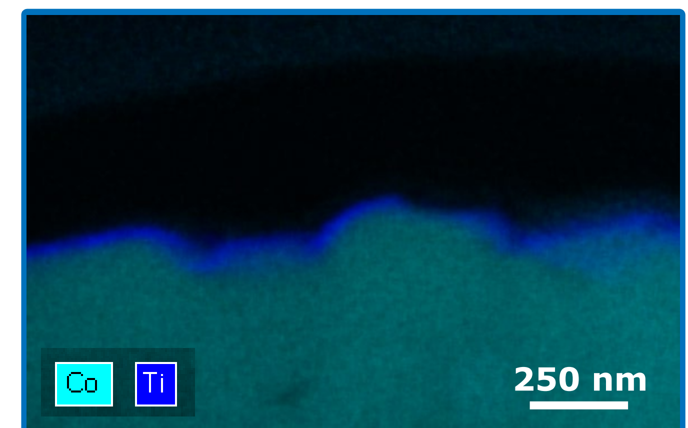
STEM 200kV
60 mm² EDS detector



SEM 20kV
60 mm² EDS detector



SEM 20kV
FlatQuad detector



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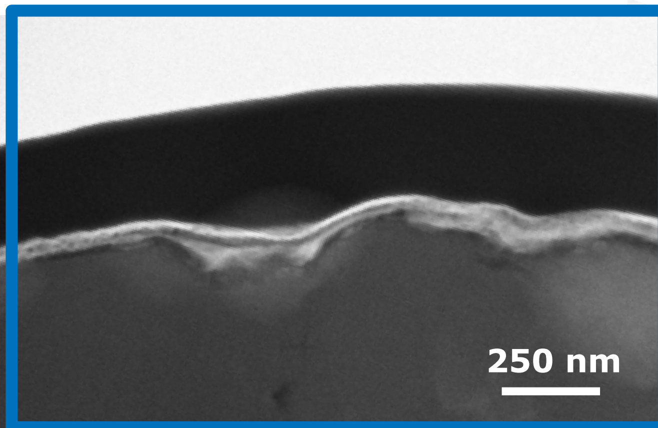
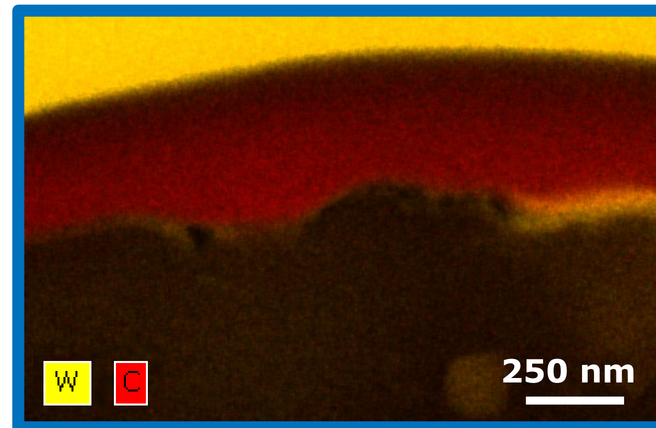
Comparison of the same sample STEM - SEM

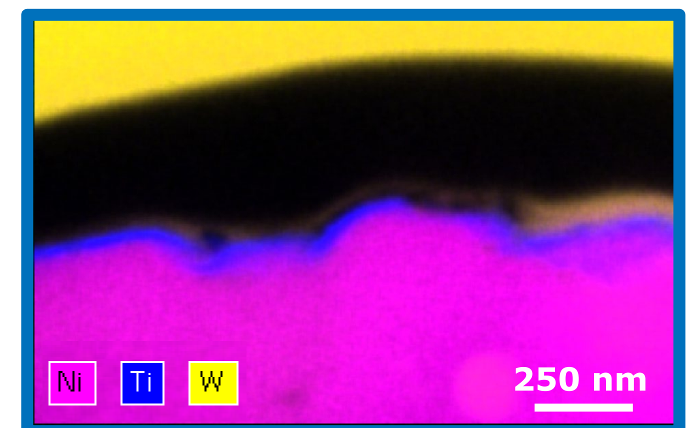
STEM 200kV
60 mm² EDS detector



SEM 20kV
60 mm² EDS detector



SEM 20kV
FlatQuad detector



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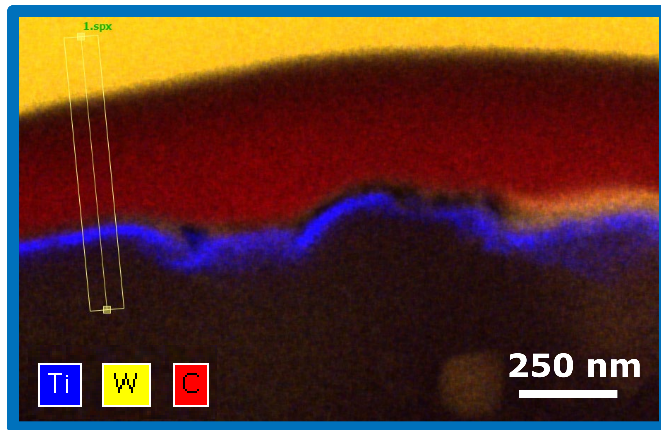
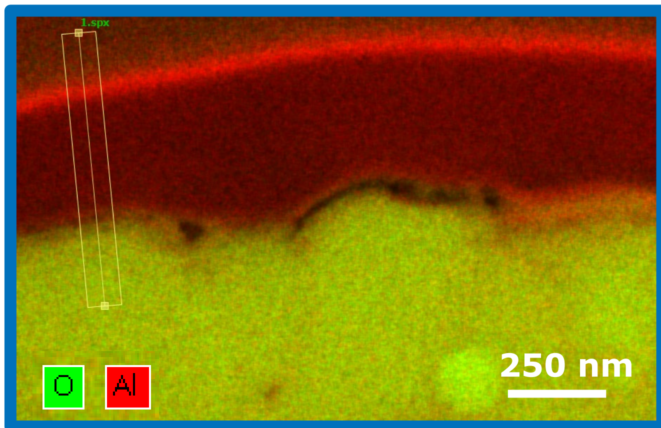
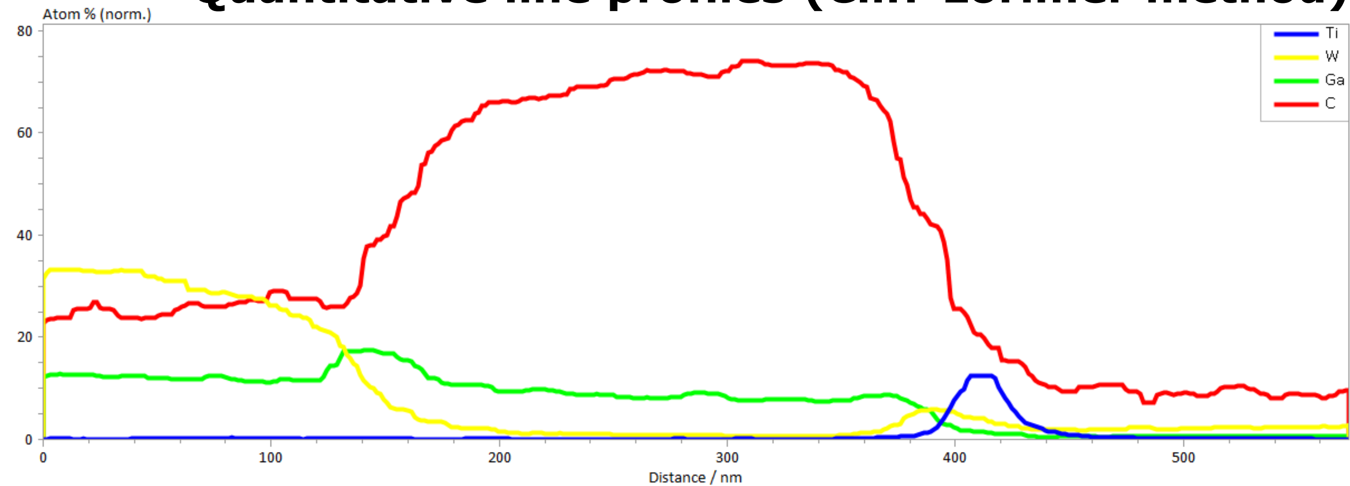
What additional information EDS reveals

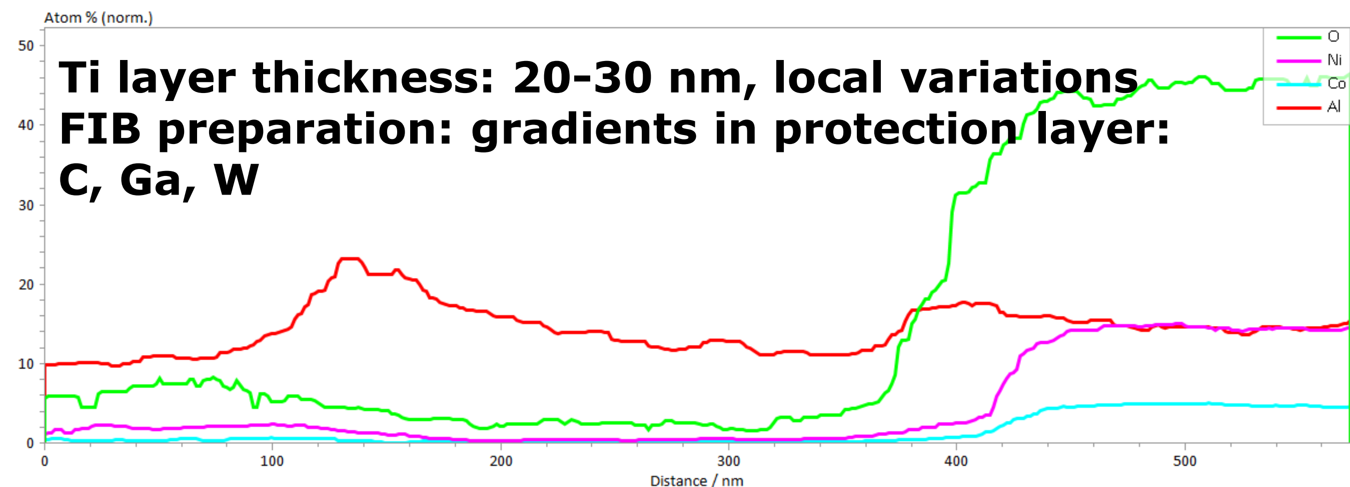
SEM 20kV
60 mm² EDS detector





Quantitative line profiles (Cliff-Lorimer method)





Ti layer thickness: 20-30 nm, local variations
FIB preparation: gradients in protection layer: C, Ga, W

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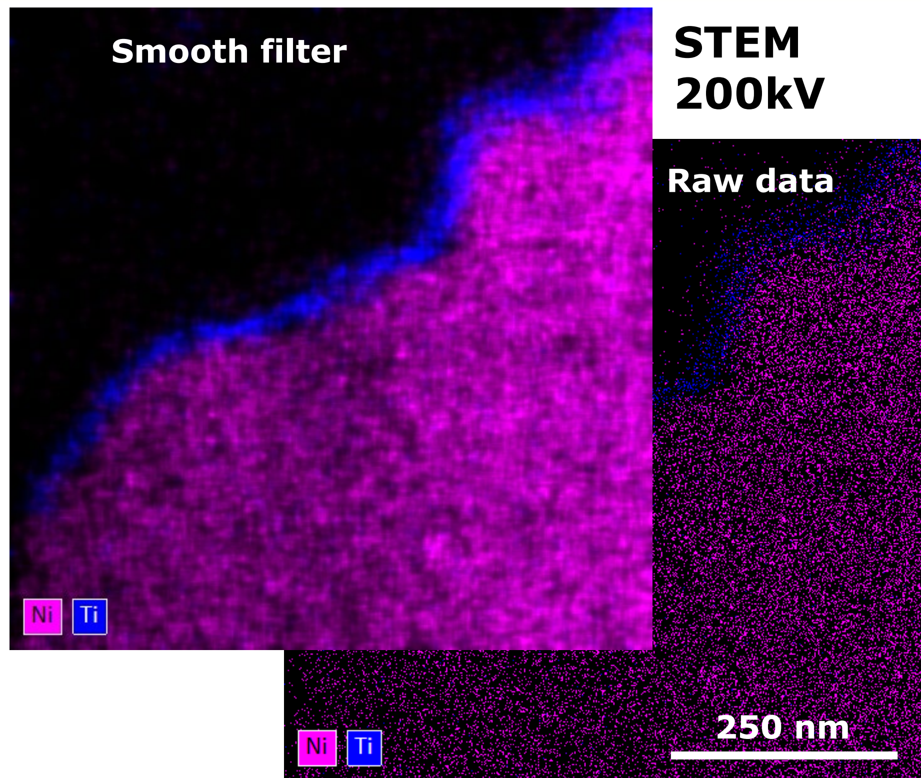
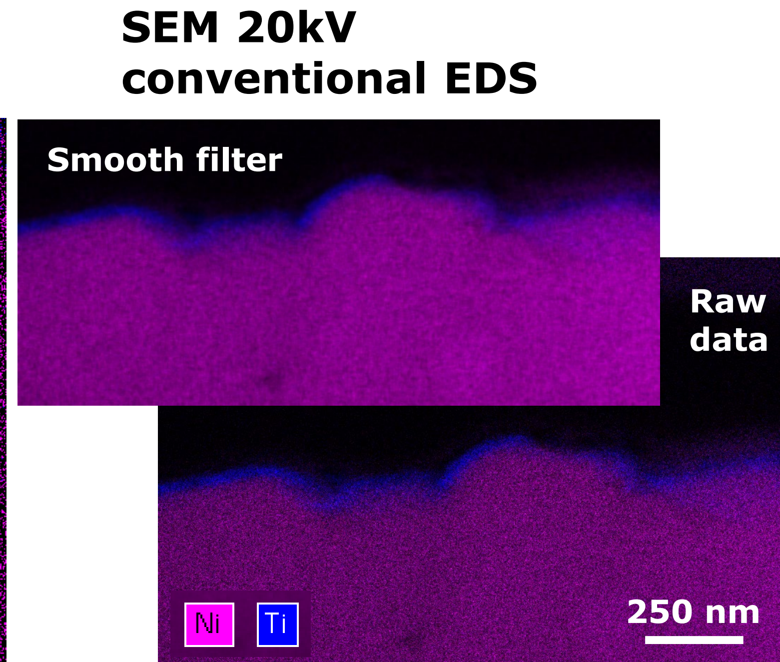
STEM-EDS vs. SEM-EDS vs. SEM-FlatQuad EDS

STEM 200kV



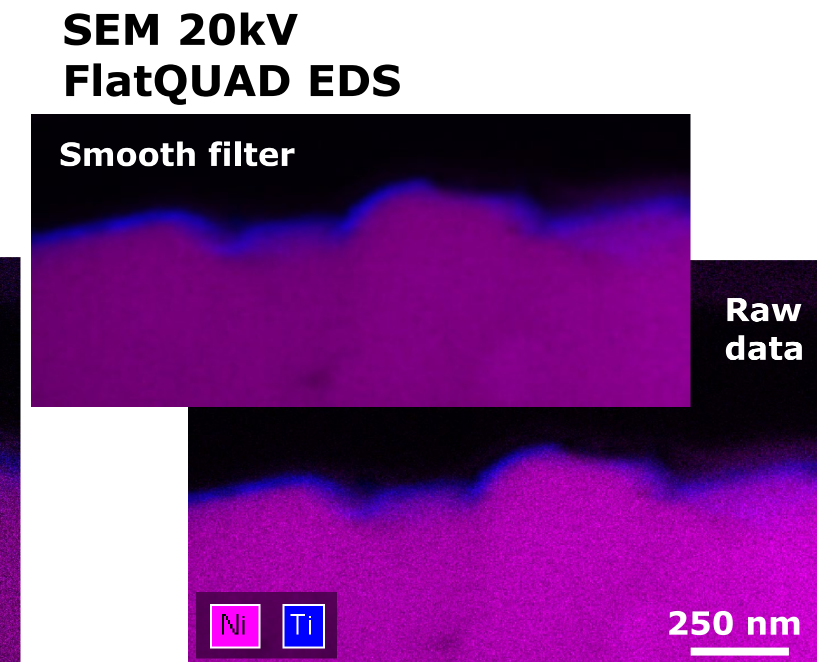
Higher spatial resolution
Lower beam currents
-> less signal (filtering needed) or longer measurements

SEM 20kV conventional EDS



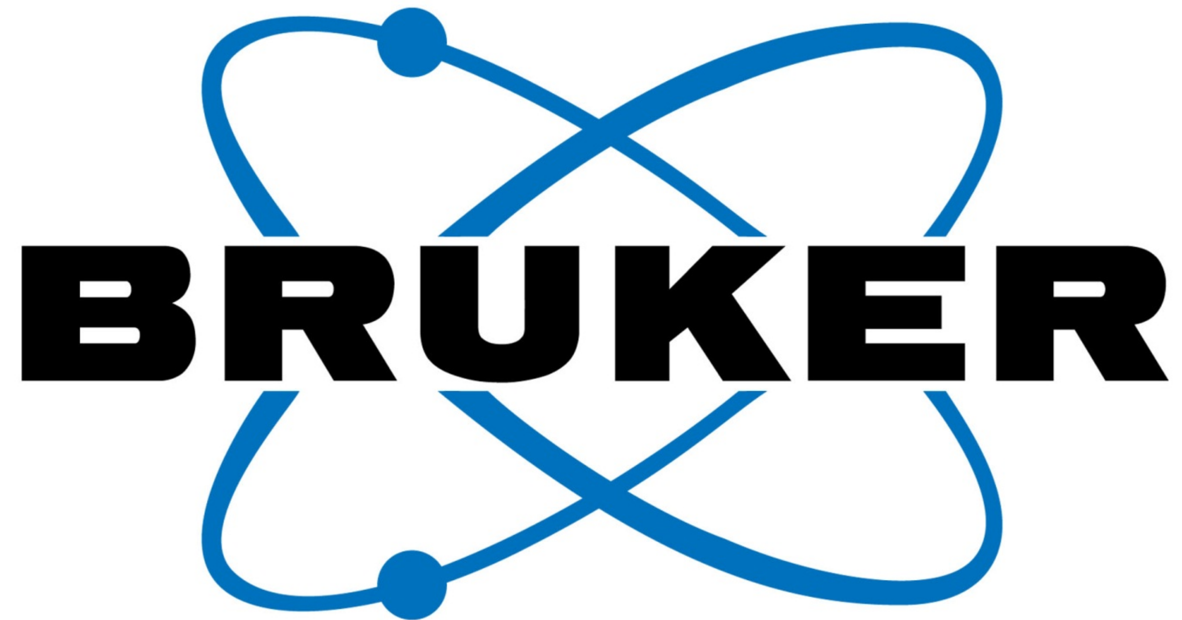
Lower spatial resolution due to lower kV
Lower solid angle due to larger sample-detector distance
Higher beam currents -> more signal or shorter measurements

SEM 20kV FlatQUAD EDS



Maps with very high statistics
EDS spatial resolution not affected due to longer WD

Sample and data courtesy: Michael Malaki, Shamail Ahmed, Materials Sciences Center, Philipps University Marburg



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